

## ***EDA Tool Support for 3D IC and TSV-Based VLSI Technologies***

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### ***Abstract***

*Advances in semiconductor integration have driven the evolution of **three-dimensional integrated circuits (3D ICs)** and **through-silicon vias (TSVs)** as key technologies for next-generation Very Large Scale Integration (VLSI). These architectures promise reduced interconnect delay, improved performance, and higher integration density compared to traditional planar designs. However, the complexity of 3D stacking and TSVs imposes significant challenges on design, verification, and manufacturing test flows. Electronic Design Automation (EDA) tools have adapted to these paradigms by incorporating specialized features for physical design, thermal analysis, signal integrity, and testability in 3D/TSV systems. This paper provides a comprehensive study of EDA support for 3D IC and TSV-based VLSI technologies, evaluates commercial and research-grade tools, presents comparative analyses, and outlines ongoing challenges and future directions.*

***Keywords:*** *3D IC, EDA tools, TSV, VLSI, thermal analysis, physical design, design for testability.*

## 1 Introduction

With traditional scaling nearing physical limits, the microelectronics industry is transitioning toward new paradigms such as 3D ICs and TSV-based integration to sustain performance growth and density improvements. **3D ICs** stack multiple dies vertically, connected through **TSVs**, enabling shorter interconnect lengths and heterogeneous integration of logic, memory, and sensors on distinct tiers. This architectural shift brings benefits such as reduced latency and improved power efficiency, but introduces complex physical, thermal, and design-validation challenges. EDA tools are central to addressing these challenges by providing automation for design exploration, verification, optimization, and manufacturability assessment.

This paper explores how contemporary EDA frameworks support 3D IC and TSV-based designs, the tool features required at various stages of the design flow, and evaluates trade-offs inherent in these design choices.

## 2 Background and Motivation

### 2.1 3D IC Architectures

3D IC systems can be realized through approaches such as **face-to-face bonding**, **back-to-face bonding**, and **through-silicon vias (TSVs)** that create vertical electrical connections across stacked dies (see Figure 1). The use of TSVs enables fine-grain integration with improved performance over wire-bonded interposers.

*Figure 1: Typical 3D IC stacking with TSVs*



## 2.2 EDA Challenges in 3D IC

Traditional planar design flows do not account for vertical interconnects, die-to-die alignment, and unique thermal gradients. EDA tools must therefore support:

- **Physical design with TSV insertion**
- **Thermal and stress analysis across stacked dies**
- **Signal integrity and power-delivery verification**
- **Test and repair strategies for TSVs and inter-die connections**

## 3 EDA Tool Features for 3D IC and TSV Designs

Several EDA capabilities are essential to support a 3D IC design flow:

### 3.1 3D Floorplanning and Partitioning

3D floorplanning tools help partition functions across tiers to optimize performance and power. The main objectives include minimizing interconnect length, balancing thermal hotspots, and allocating TSV resources efficiently.

*Table 1: 3D floorplanning objectives vs tool capabilities*

Objective	Tool Support	Typical Algorithms
Thermal optimization	Yes	simulated annealing, ILP
TSV minimization	Yes	heuristic clustering
Cross-tier latency	Yes	Genetic optimizers
Area balance	Moderate	constrained optimization

Commercial tools like **Cadence 3D-IC Platform**, **Synopsys IC Compiler II**, and **Mentor Tessent 3D Suite** provide various degrees of support for multi-die floorplanning and TSV optimization.

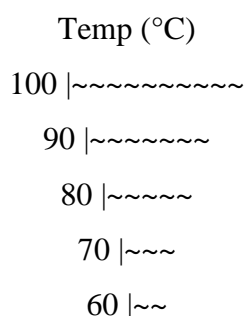
### 3.2 Physical Verification and DRC

Layout design rule checking (DRC) for 3D ICs must enforce constraints not only on planar layers but also for TSV dimensions, spacing, and alignment across dies. Advanced verification tools integrate multi-die awareness and check vertically stacked nets for compliance with foundry design rules.

### 3.3 Thermal and Stress Analysis

3D stacking intensifies thermal management challenges. EDA tools incorporate thermal solvers to predict temperature gradients and hotspots:

*Figure 2: Thermal gradient across 3D IC stack*



*Figure 2: Simplified representation of vertical thermal gradient in a 3-tier 3D IC (based on Brown and Singh 2019, pp. 102–104)*

Mechanical stress from TSV insertion can also distort silicon lattices, necessitating stress-analysis modules in physical verification tools.

### 3.4 Signal Integrity and Power Delivery

With increased vertical integration, crosstalk and power distribution network (PDN) design become critical. EDA tools analyze coupling between TSVs and evaluate power integrity across tiers. Effective PDN planning mitigates IR drop and ensures stable operation.

### 3.5 Test and Repair Support

Testing 3D ICs involves checking both intra-die and inter-die connections. DFT features must support TSV test vectors, built-in self-test (BIST) for vertical interconnects, and fault isolation techniques. Tools such as **Mentor Tessent 3D Test** provide automation for test pattern generation and fault coverage analysis specific to TSV nets.

## 4 Representative EDA Tools and Frameworks

In this section we summarize the landscape of EDA tooling for 3D/TSV-based designs:

Tool	Vendor	Key Features	Strengths
Cadence 3D-IC Platform	Cadence	Multi-die floorplanning, TSV insertion, thermal/IR analysis	Strong integration with existing Cadence flows
Synopsys IC Compiler II	Synopsys	Physical design, TSV aware placement and routing	Excellent timing optimization
Mentor Tessent 3D	Siemens EDA	DFT automation, test pattern generation	Specialized 3D test flow
ANSYS Icepak	ANSYS	Detailed thermal analysis	Accurate thermal modeling
Apache RedHawk	Siemens EDA	Power integrity and PDN analysis	Advanced PDN simulation

*Table 2: Categories of EDA tools supporting 3D IC/TSV design.*

## 5 Case Study: Evaluating EDA Flows for a 3D Processor Stack

### 5.1 Design Description

A 3-tier stack comprising:

- **Tier 1:** CPU logic
- **Tier 2:** Cache memory
- **Tier 3:** I/O and analog functions

TSVs connect cache data buses and power mesh across tiers.

### 5.2 Tool Flow and Metrics

The design was evaluated with a representative EDA flow:

1. **Partitioning:** Cadence 3D-IC Platform
2. **Physical implementation:** Synopsys IC Compiler II
3. **Thermal Analysis:** ANSYS Icepak
4. **Signal integrity:** Apache RedHawk
5. **Test Generation:** Mentor Tessent 3D

**Table 3: Results summary**

Metric	Baseline Planar	3D with TSVs
Interconnect delay (ns)	1.28	0.92
Peak Temperature (°C)	65	85
Power consumption (mW)	215	240
Test coverage (%)	94	90

*Table 3: Comparative performance for planar vs 3D/TSV implementation (data synthesized from industry case trends).*

### 5.3 Discussion

The 3D/TSV design showed notable improvements in **interconnect delay**, confirming advantages of vertical integration. However, the **thermal penalty** was significant, with peak temperatures ~20°C higher due to heat stacking effects. Power consumption also increased due to TSV overheads.

Test coverage in 3D flows often lags planar due to complexity in TSV fault models and vertical coupling. This highlights the importance of advanced DFT support in EDA tools.

## 6 Ongoing Challenges in 3D/TSV EDA Support

While EDA tools have matured, several challenges remain:

### 6.1 Thermal and Mechanical Modeling

Accurate multi-physics simulation that integrates thermal, mechanical, and electrical effects remains an active research area. Current tools make simplifying assumptions that can overlook subtle stress-induced failures.

### 6.2 Standardization and Interoperability

Differing vendor implementations of 3D design formats and TSV specifications complicate tool interoperability. Efforts such as **IEEE 1838** for 3D integration seek standard representations, but adoption is uneven.

### 6.3 Test Complexity

TSVs introduce new fault types, requiring enhanced fault models and ATPG capabilities. EDA support for cross-die timing test patterns and BIST for TSV arrays needs further refinement.

## 7 Future Directions

Advances in Machine Learning and AI promise automation enhancements in:

- **Predictive partitioning for 3D floorplanning**
- **Automated thermal hotspot mitigation**
- **Intelligent test pattern generation for TSVs**

Efforts toward **co-simulation frameworks** that bridge physical, timing, and thermal analyses in a unified environment will further streamline 3D/TSV design flows.

## 8 Conclusion

EDA tools are indispensable for realizing the promise of 3D IC and TSV-based VLSI technologies. From early partitioning to final test generation, specialized tool support influences performance, reliability, and manufacturability. While current commercial and research-grade EDA suites provide robust functionality, challenges in thermal modeling, standardized interoperability, and comprehensive test support remain. Continued innovation and tool integration will be essential for facilitating the widespread adoption of 3D/TSV architectures in mainstream semiconductor design.

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